L Number	Hits	Search Text	DB	Time stamp
1	48	plasma and (RF or radiofrequency) and impedance and capacitors and resistor and "matching circuit"	USPAT; EPO; JPO; IBM_TDB	2002/11/23 12:33
5	1381	plasma and (RF or radiofrequency) and impedance and capacitors	USPAT; EPO; JPO; IBM_TDB	2002/11/23 12:38
6	28205	resistor same "voltage drop"	USPAT; EPO; JPO; IBM_TDB	2002/11/23 10:59
8	619	plasma and (RF or radiofrequency) and impedance and capacitors and resistor	USPAT; EPO; JPO; IBM_TDB	2002/11/23 11:03
9	372	(plasma and (RF or radiofrequency) and impedance and capacitors and resistor) and etch$5	USPAT; EPO; JPO; IBM_TDB	2002/11/23 12:21
11	35	(plasma and (RF or radiofrequency) and impedance and capacitors and resistor) and endpoint	USPAT; EPO; JPO; IBM_TDB	2002/11/23 12:21
12	12	plasma same (RF or radiofrequency) same ("matching circuit" near4 voltage)	USPAT; EPO; JPO; IBM_TDB	2002/11/23 12:35
13	222	plasma and (RF or radiofrequency) and impedance and capacitors and (resistor near4 voltage)	USPAT; EPO; JPO; IBM_TDB	2002/11/23 12:38